IN THE CLAIMS

Please amend the claims as follows:

- 1. (original) A method for producing a preform from synthetic quartz glass by means of a plasma-assisted deposition method in that a hydrogen-free media flow containing a glass starting material and a carrier gas is supplied to a multi-nozzle deposition burner, the glass starting material is introduced by means of the deposition burner into a plasma zone and is oxidized therein while forming SiO₂ particles, and the SiO₂ particles are deposited on a deposition surface while being directly vitrified, characterized in that the media flow is focused by means of the deposition burner (1) towards the plasma zone (4).
- (original) The method according to claim 1, characterized in that the media flow is focused onto the plasma zone (4) by means of a media nozzle (7) of the deposition burner
 (1) that is tapering towards the plasma zone (4).
- 3. (original) The method according to claim 2, characterized in that when exiting from the media nozzle (7) the media flow is enveloped by an oxygen-containing working gas flow.
- 4. (original) The method according to claim 3, characterized in that the working gas flow turbulently exits from a first working gas nozzle (14) of the deposition burner (1) that is designed as a diffuser.

- 5. (currently amended) The method according to claim 3 [or-4], characterized in that when exiting from the working gas nozzle (14) the working gas flow is enveloped by at least one oxygen-containing separating gas flow exiting from an annular gap nozzle (17) coaxially surrounding the working gas nozzle (14).
- 6. (currently amended) The method according to [any one of claims] claim 3 [to 5], characterized in that the plasma zone (4) is produced by means of high-frequency excitation (3) inside a burner tube (2) into which a mixture of media flow and working gas flow is introduced.
- 7. (currently amended) The method according to <u>claim 1</u> [any one of the preceding elaims], characterized in that the media flow contains silicon tetrachloride (SiCl₄) and nitrogen as the carrier gas.
- 8. (currently amended) The method according to <u>claim 1</u> [any one of the preceding elaims], characterized in that the glass starting material contains a fluorine-containing component.
- 9. (currently amended) A device for performing the method according to [any one of elaims] claim 1 [to-7], comprising an excitation source for producing a plasma zone, and a multi-nozzle deposition burner which has a central axis and which is provided with a media nozzle for the supply of a media flow to the plasma zone, characterized in that the media nozzle (7) is configured to focus towards the plasma zone (4).

- 10. (original) The device according to claim 9, characterized in that the media nozzle (7) tapers in a tapering area (6) towards the plasma zone (4).
- 11. (original) The device according to claim 10, characterized in that the tapering area (6) has a length of at least 5 mm, preferably at least 8 mm.
- 12. (currently amended) The device according to [any one of the preceding claims] claim 9 [to 11], characterized in that the media nozzle (7) has a nozzle opening with a diameter ranging between 4.5 mm and 6.5 mm, preferably between 5.0 mm and 6.0 mm.
- 13. (currently amended) The device according to [any one of claims] claim 9 [to 12], characterized in that the media nozzle (7) is designed as a central middle nozzle and is coaxially surrounded by a working gas nozzle (14) in the form of an annular gap which is designed as a diffuser and continuously expands in an expansion area towards the plasma zone (4).
- 14. (original) The device according to claim 13, characterized in that the expansion area has a length of at least 5 mm, preferably at least 8 mm.
- 15. (currently amended) The device according to [any one of claims] claim 12 [to 14], characterized in that the media nozzle (7) has a nozzle opening which extends in a first nozzle plane extending in a direction perpendicular to the central axis (9), and that the

working gas nozzle (14) has a nozzle opening which extends in a second nozzle plane extending in a direction perpendicular to the central axis, the first nozzle plane, when viewed in the direction of flow, being arranged upstream of the second nozzle plane by a length between 5 mm and 35 mm, preferably between 13 mm and 33 mm.

- 16. (currently amended) The device according to <u>claim 9</u> [any one of the preceding device <u>claims</u>], characterized in that the media nozzle (7) is formed by a quartz glass tube.
- 17. (currently amended) The device according to <u>claim 9</u> [any one of the preceding device <u>claims</u>], characterized in that the media nozzle (7) is designed as a central middle nozzle and is coaxially surrounded by at least two annular gap nozzles (14; 17) for the supply of oxygen to the plasma zone (4).